

Title (en)

COSMETIC COMPOSITIONS COMPRISING AN ANTIMICROBIAL SYSTEM WITH REDUCED EYE IRRITATION OR DISCOMFORT

Title (de)

KOSMETISCHE ZUSAMMENSETZUNGEN MIT EINEM ANTIMIKROBIELLEN SYSTEM MIT VERRINGERTER AUGENREIZUNG ODER VERRINGERTEM SCHMERZ

Title (fr)

COMPOSITIONS COSMÉTIQUES COMPRENANT UN SYSTÈME ANTIMICROBIEN PRÉSENTANT UNE IRRITATION OU UNE GÊNE RÉDUITE DE L'?IL

Publication

**EP 4221665 A1 20230809 (EN)**

Application

**EP 21791204 A 20210930**

Priority

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- US 2021052787 W 20210930

Abstract (en)

[origin: WO2022072585A1] A cosmetic composition includes an antimicrobial system that includes an antimicrobial agent comprising 4-hydroxyacetophenone and one or more additional antimicrobial agents comprising piroctone olamine. The antimicrobial system can be used in a cosmetic composition wherein the composition is a makeup removal composition that is one of an O/W emulsion, a W/O emulsion, a micellar water, a makeup removing wipe, or a two-phase (or multi-phase) composition. The antimicrobial system may be free or essentially free of any one or more of parabens, alcohols, formaldehyde, and formaldehyde-derived compounds. In some particular embodiments, the composition is free or essentially free of parabens, formaldehyde, formaldehyde-derived compounds, pentylene glycol, phenoxyethanol, hexylglycerin, ethylhexylglycerin, octylglycerin, benzylglycerin, 3-heptoyl-2,2-propandiol, and 1,2-hexandiol.

IPC 8 full level

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